

<b>Notice of References Cited</b>	Application/Control No. 10/075,297	Applicant(s)/Patent Under Reexamination LIN, SHIH CHIEH	
	Examiner Un C Cho	Art Unit 2687	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2002/0128050	09-2002	Hong et al.	455/572
	B	US-6,501,246	12-2002	You et al.	320/114
	C	US-3,749,946	07-1973	Von Ruti, Jurg	310/319
	D	US-5,177,426	01-1993	Nakanishi et al.	320/134
	E	US-6,643,527	11-2003	Satoh et al.	455/574
	F	US-6,821,670	11-2004	Hsueh, Chih-Yuan	429/98
	G	US-6,528,969	03-2003	Tung et al.	320/103
	H	US-5,334,076	08-1994	Shinozuka, Morio	446/456
	I	US-6,433,508	08-2002	Yang, Tai-Her	320/103
	J	US-5,343,136	08-1994	Yamaguchi et al.	320/103
	K	US-2003/0050102	03-2003	Roh, Ji-Won	455/573
	L	US-2002/0147036	10-2002	Taguchi et al.	455/573
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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	V	
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	X	

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